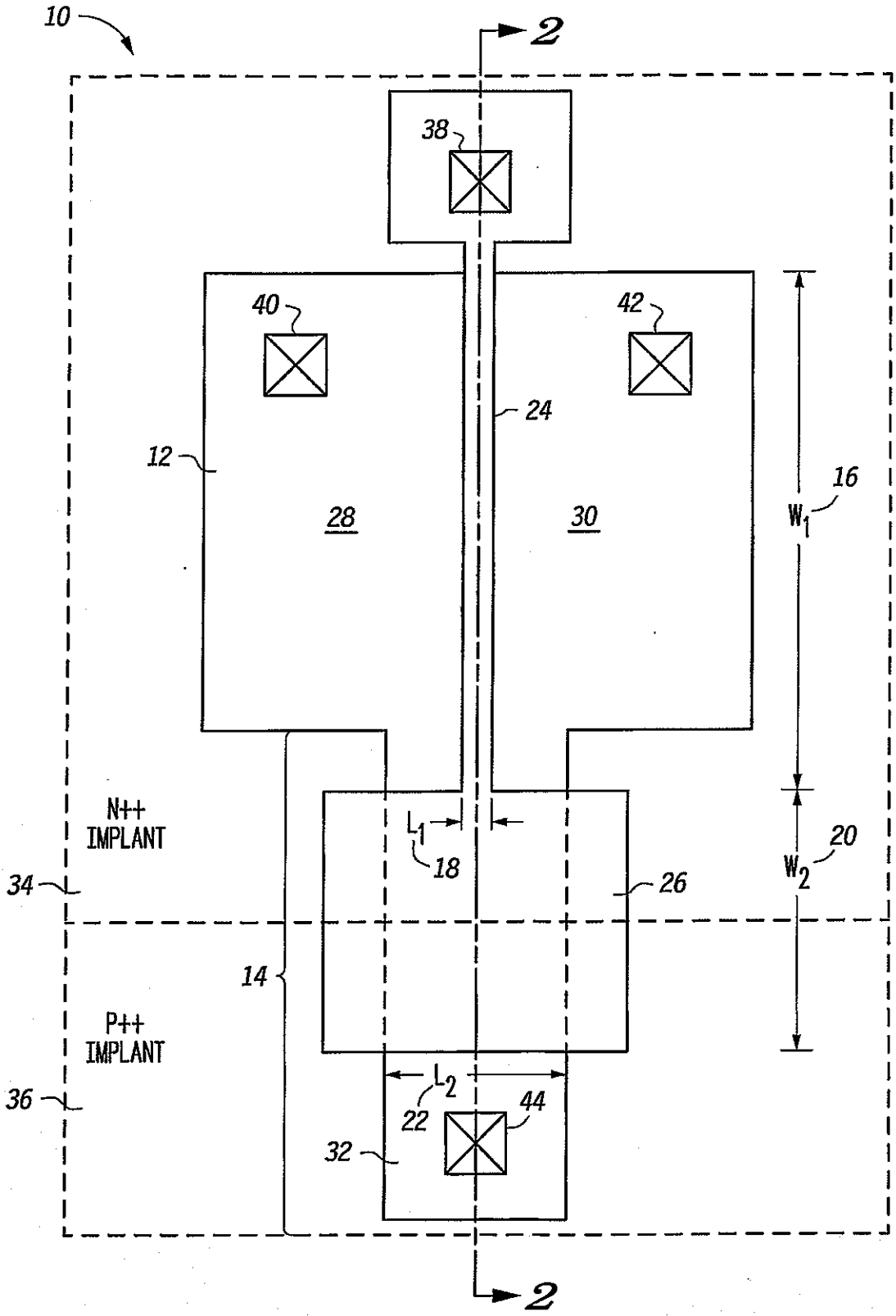


FIG. 1
-PRIOR ART-

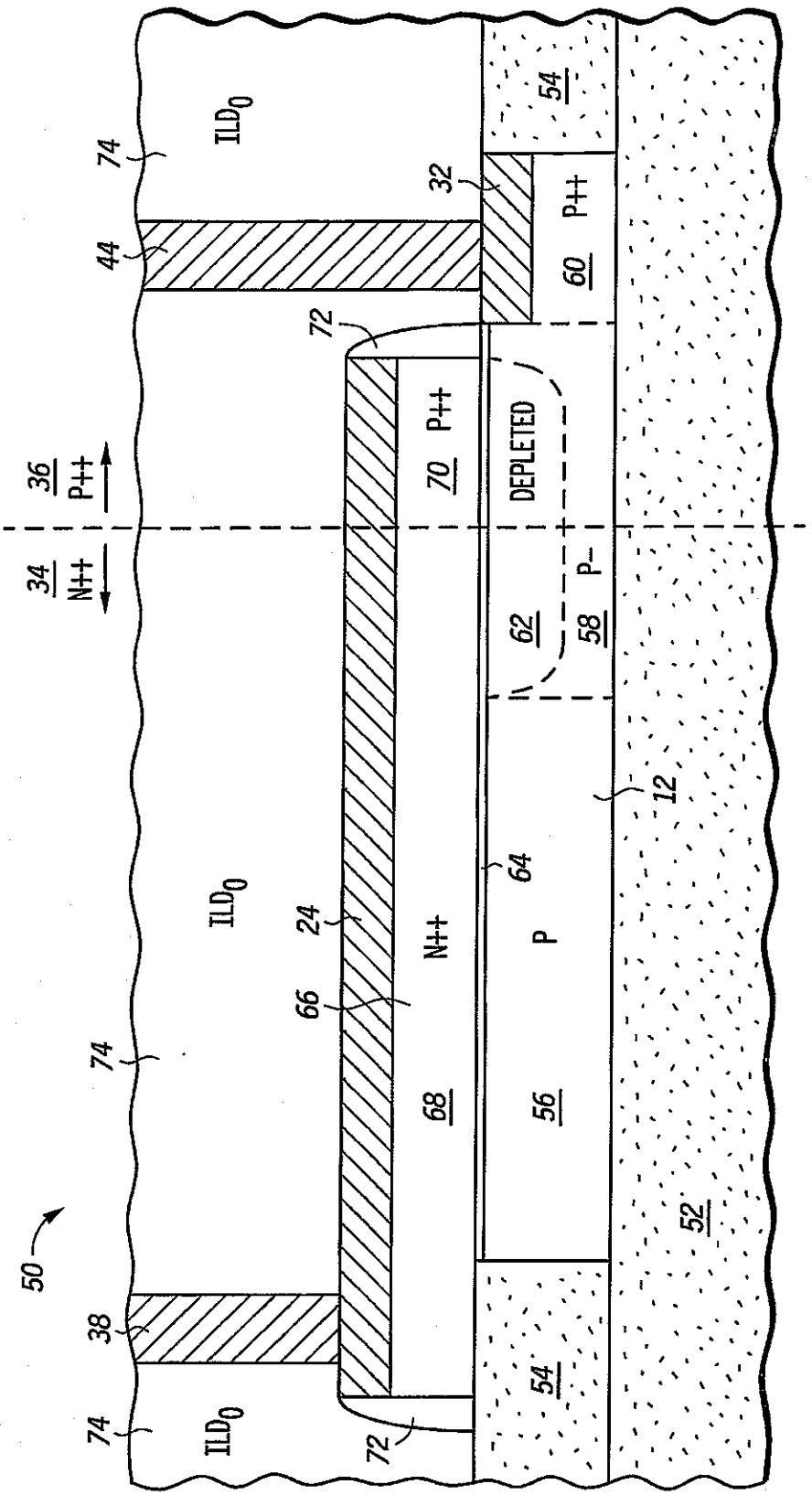


FIG. 2
-PRIOR ART-

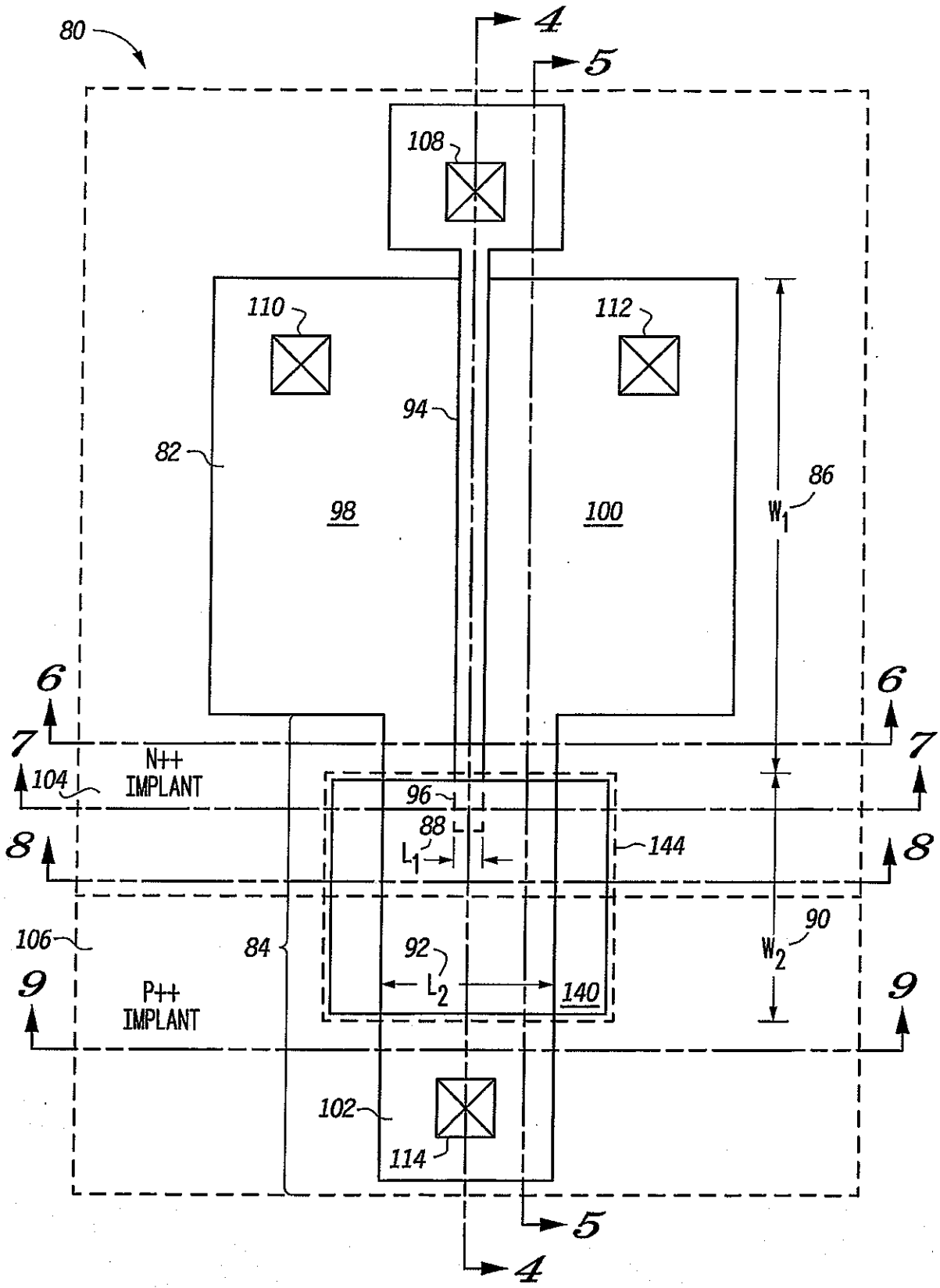

80
4
5
108
110
112
94
82
98
100
86
W_1
6
7
N++
IMPLANT
104
96
88
L_1
144
8
106
84
92
L_2
140
90
W_2
9
P++
IMPLANT
102
114

FIG. 3

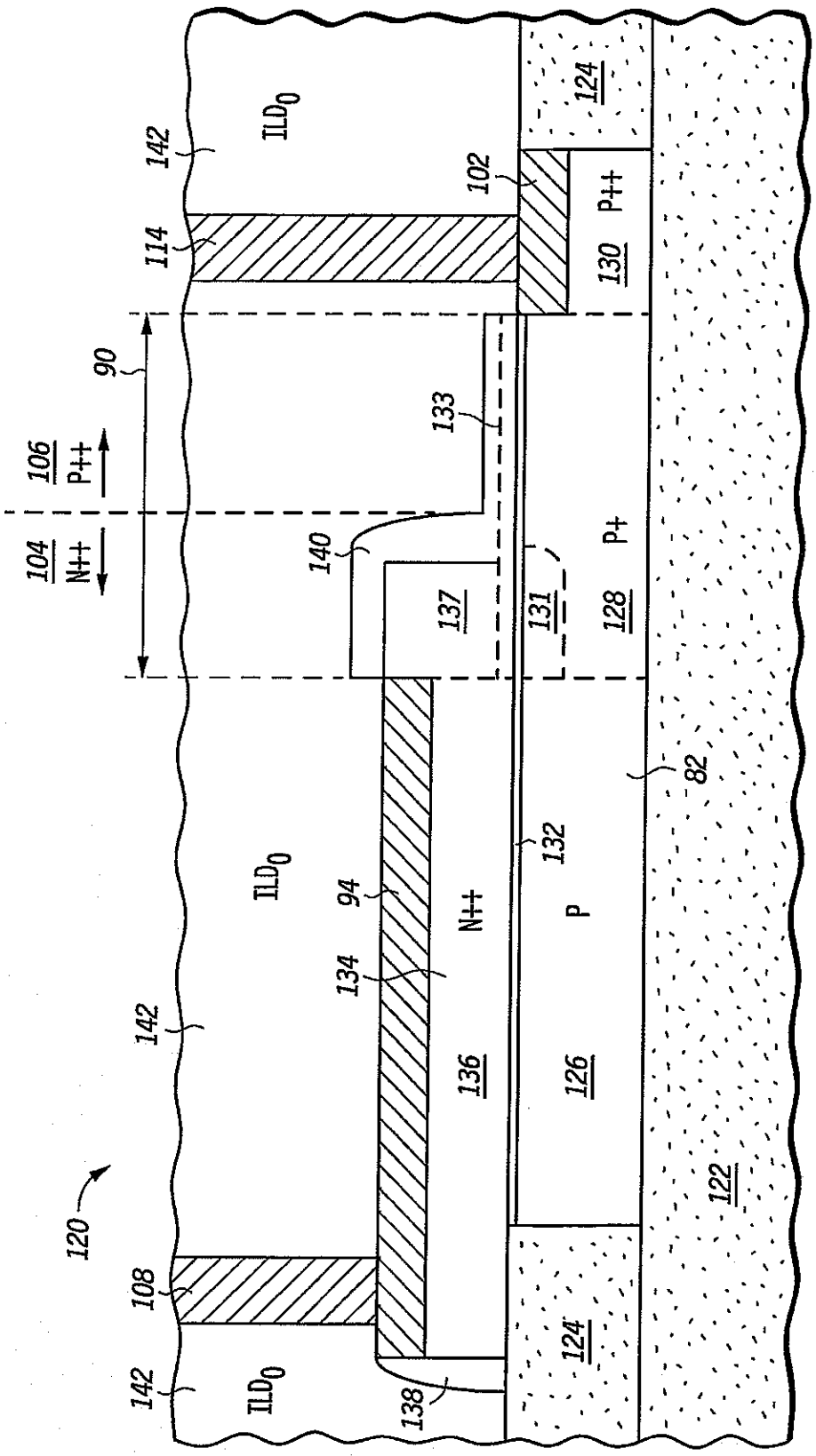

ILD0
142
114
102
124
P++
130
90
106
P++
104
N++
133
140
137
131
P+
128
82
132
94
134
N++
P
136
126
122
120
108
124
138

FIG. 4

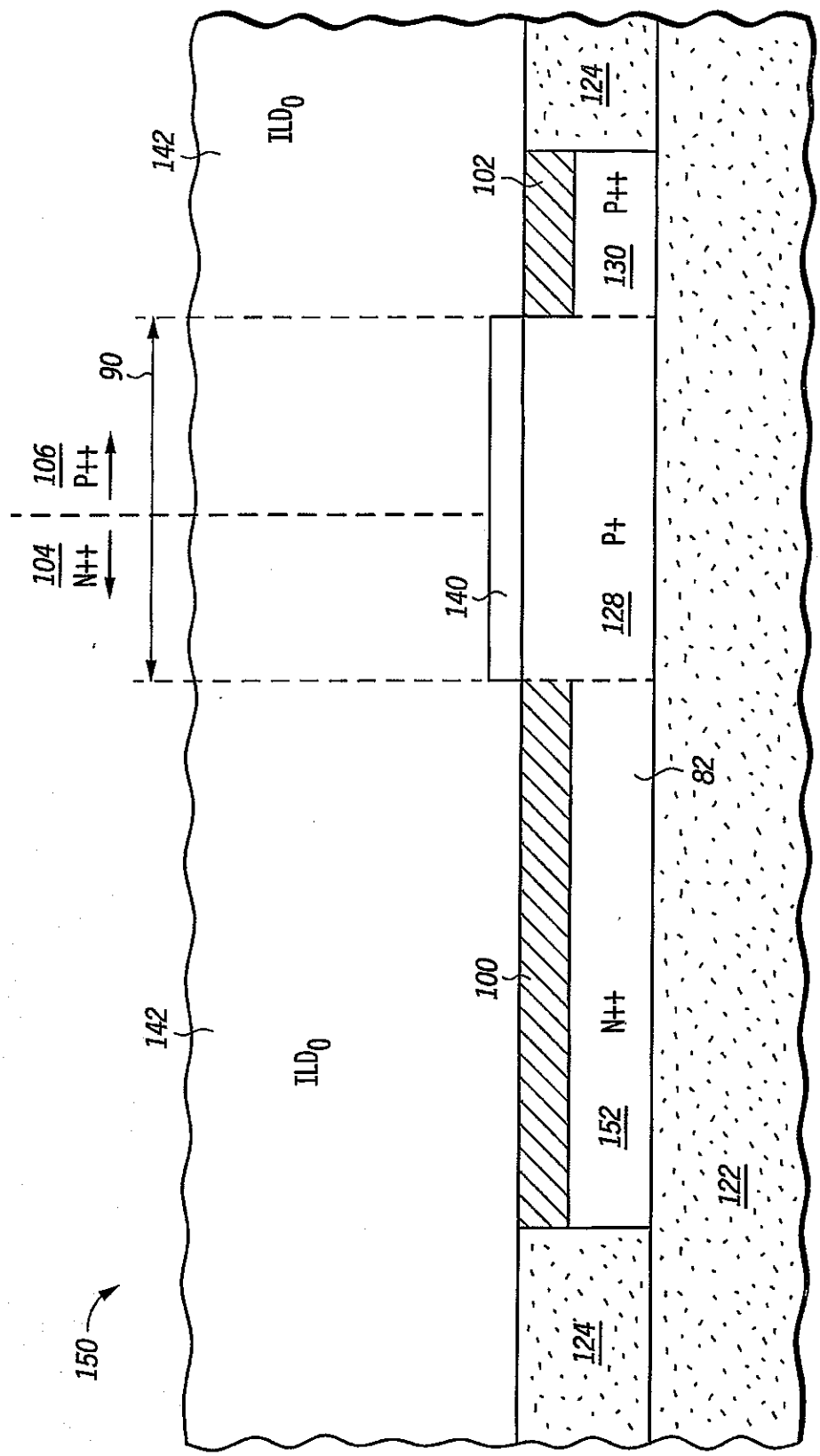

150
142
ILD0
142
ILD0
124
102
P++
130
90
106
P++
104
N++
140
P+
128
82
100
N++
152
122
124

FIG. 5

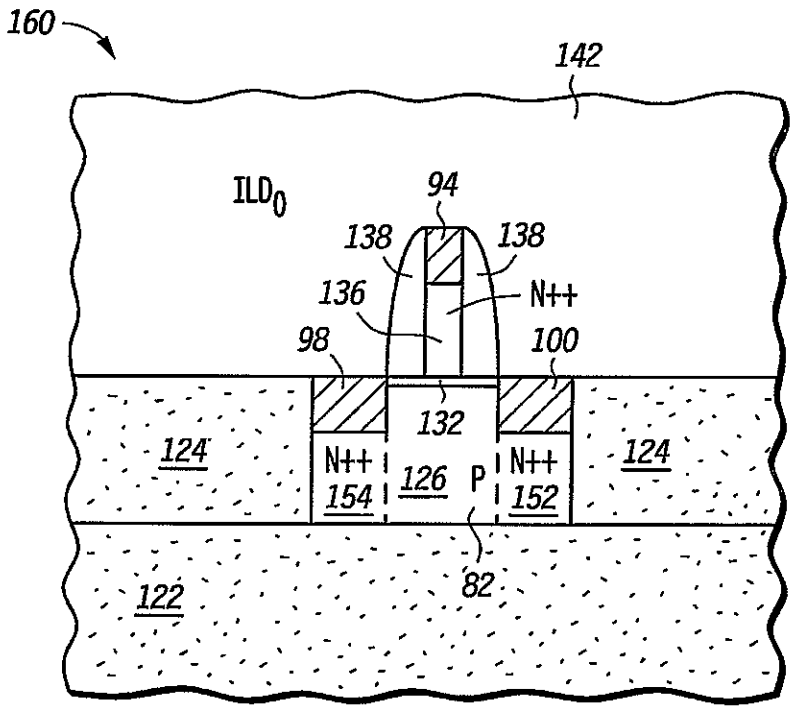

160
142
ILD0
94
138
138
136
N++
98
100
132
124
N++
154
126
P
N++
152
124
122
82

FIG. 6

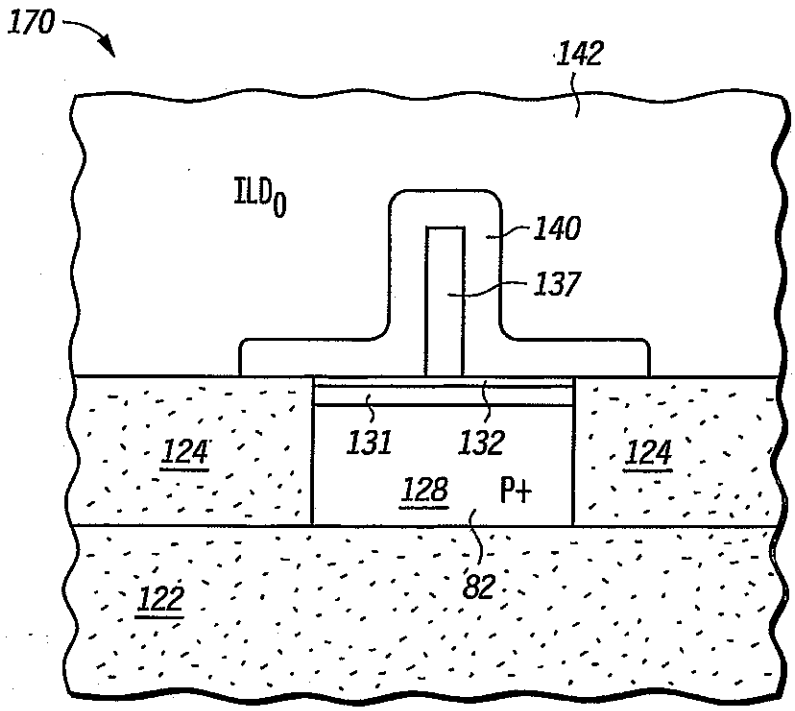

170
142
ILD0
140
137
131
132
124
128
P+
124
122
82

FIG. 7

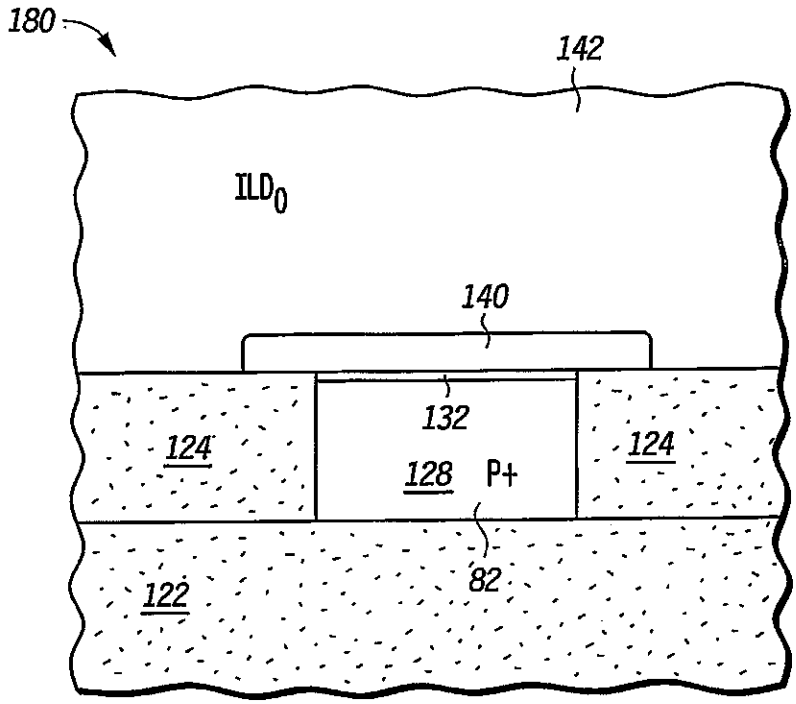

180
142
ILD0
140
132
124
128 P+
124
82
122

FIG. 8

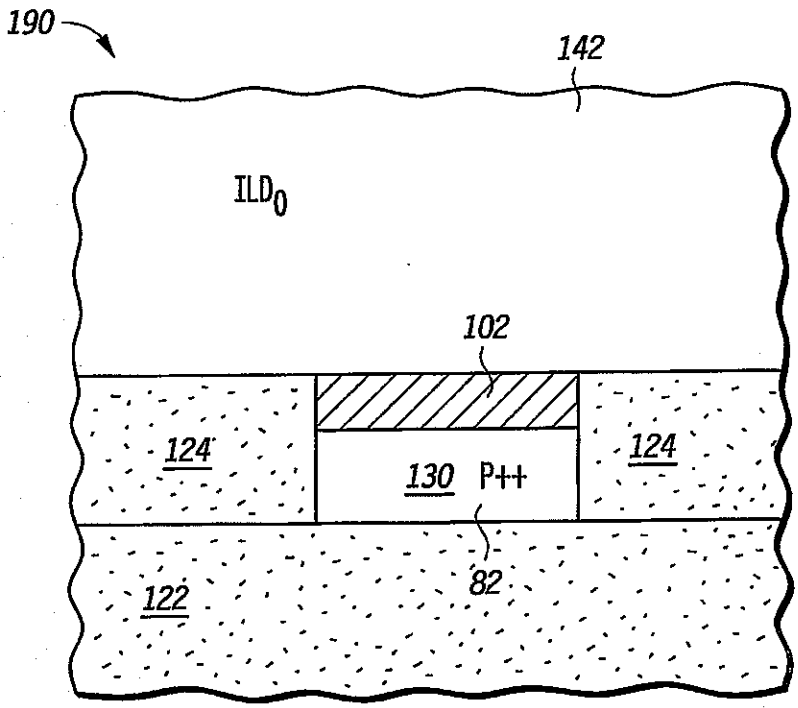

190
142
ILD0
102
124
130 P++
124
82
122

FIG. 9

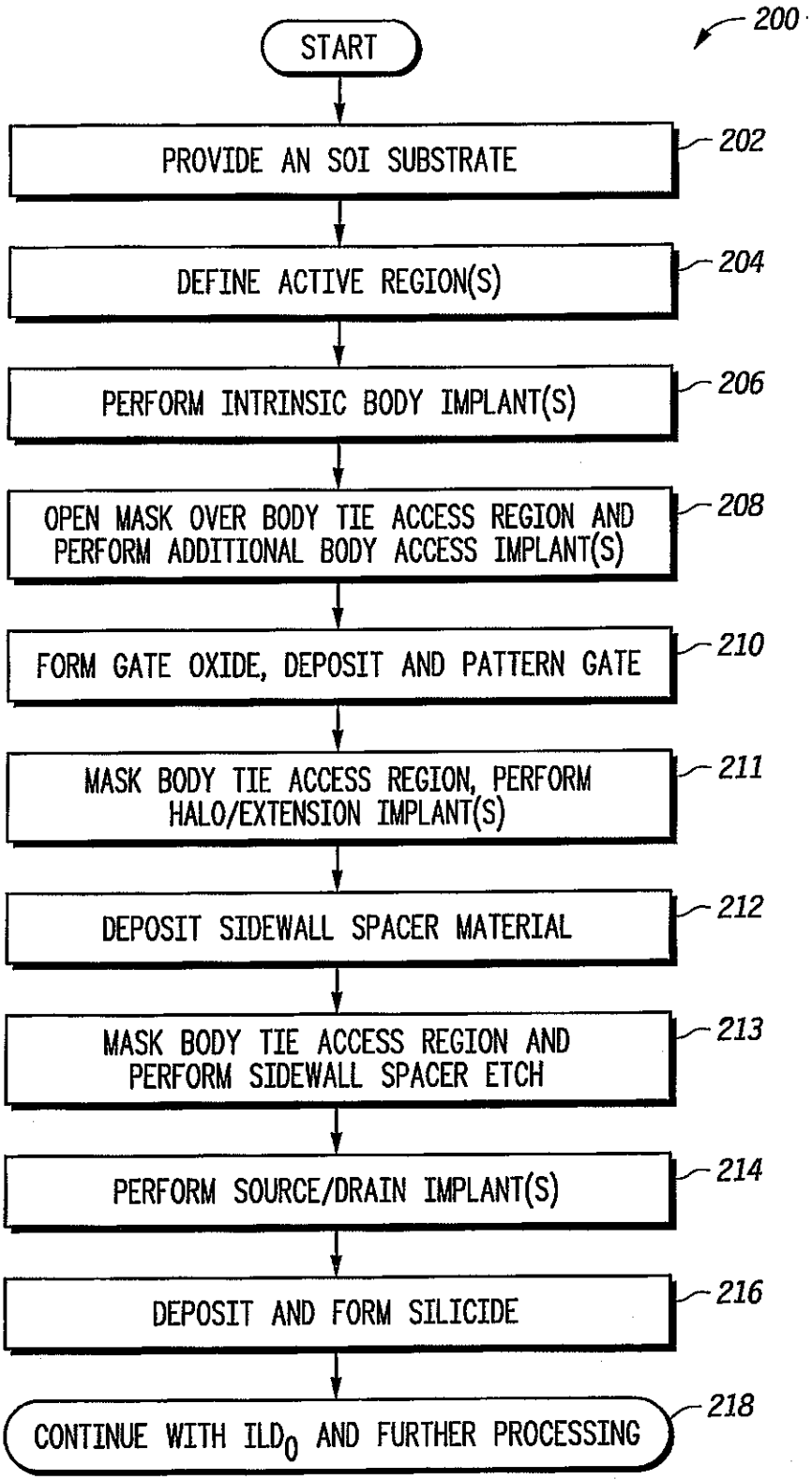

200
START
PROVIDE AN SOI SUBSTRATE
202
DEFINE ACTIVE REGION(S)
204
PERFORM INTRINSIC BODY IMPLANT(S)
206
OPEN MASK OVER BODY TIE ACCESS REGION AND PERFORM ADDITIONAL BODY ACCESS IMPLANT(S)
208
FORM GATE OXIDE, DEPOSIT AND PATTERN GATE
210
MASK BODY TIE ACCESS REGION, PERFORM HALO/EXTENSION IMPLANT(S)
211
DEPOSIT SIDEWALL SPACER MATERIAL
212
MASK BODY TIE ACCESS REGION AND PERFORM SIDEWALL SPACER ETCH
213
PERFORM SOURCE/DRAIN IMPLANT(S)
214
DEPOSIT AND FORM SILICIDE
216
CONTINUE WITH ILD0 AND FURTHER PROCESSING
218

FIG. 10